

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of Falster et al Serial No. 10/615,127 Filed July 24, 2003 Confirmation No. 8157

For PROCESS FOR PREPARING A STABILIZED IDEAL OXYGEN PRECIPITATING SILICON WAFER

October 17, 2003

COMMISSIONER FOR PATENTS P.O. BOX 1450 ALEXANDRIA, VIRGINIA 22313-1450

SIR:

INFORMATION DISCLOSURE STATEMENT

In accordance with 37 C.F.R. 1.97 and 1.98 and MPEP 609, and in compliance with the duty of disclosure set forth in 37 C.F.R. 1.56, applicants submit copies of the references listed on the attached PTO/SB/08A for consideration by the Patent and Trademark Office in the above-entitled application and to be made of record therein.

Respectfully submitted,

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INFORMATION	DISC	LOSURE	Application Number	10/615,127		
STATEMENT B	Y AP	PLICANT	Filing Date	July 24, 2003		
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E JC8,			First Named Inventor	Falster et al		
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Sheet 1	of	4	Attorney Docket No.	MEMC TP-01-2450 (3009)		

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^{&#}x27;Unique citation designation number. ²See attached Kinds of U.S. Patent Documents. ³Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶Applicant is to place a check mark here if English language Translation is attached or place an "A" here if English language abstract is attached..

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